

Publication

**EP 0565006 A3 19940223**

Application

**EP 93105536 A 19930402**

Priority

JP 8418192 A 19920406

Abstract (en)

[origin: EP0565006A2] A method for preparing a PS plate comprises the steps of treating an anodized aluminum plate with an aqueous solution of an alkali metal silicate having a pH ranging from 10 to 13 as determined at 25 DEG C, then treating the aluminum plate with an aqueous solution of an acid having a pH ranging from 1 to 6 and applying a light-sensitive layer onto the aluminum plate thus treated. The aluminum substrate of the PS plate is only slightly dissolved in an alkaline developer and this accordingly prevents the formation of insoluble compounds or sludge effectively, during development.

IPC 1-7

**B41N 3/03**

IPC 8 full level

**B41N 3/03** (2006.01); **G03F 7/00** (2006.01)

CPC (source: EP)

**B41N 3/034** (2013.01)

Citation (search report)

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- [XD] EP 0149490 A2 19850724 - FUJI PHOTO FILM CO LTD [JP]
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- [A] FR 2202308 A1 19740503 - OCE VAN DER GRINTEN NV [NL]
- [A] DE 1118009 B 19611123 - POLYCHROME CORP
- [AD] PATENT ABSTRACTS OF JAPAN vol. 014, no. 464 (M - 1033) 9 October 1990 (1990-10-09)

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**EP 0565006 A2 19931013; EP 0565006 A3 19940223; EP 0565006 B1 19980729**; DE 69319954 D1 19980903; DE 69319954 T2 19981210; JP 2944296 B2 19990830; JP H05278362 A 19931026

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